Photomask Japan 2025 Program at a glance

As of February 25th

April 16 (Wed.)	April 17 (Thu.)		April 18 (Fri.)
Annex Hall 2F/Room 1+2	Annex Hall 2F/Room 1	Annex Hall 2F/Room 2	Annex Hall 2F/Room 1+2
9:00 - 9:10 Opening 9:10 - 11:15 Session 1 Opening Session Day 1 Keynote & Mask Patterning with material *Keynote* Presenter: Martin van den Brink (ASML) *Invited Talk* Presenter: HyunJung Hwang (SAMSUNG) Presenter: Kazunori Seki (Tekscend Photomask)	9:00 - 10:35 Session 6 Opening Session Day 2 Keynote & MDP *Keynote* Presenter: Kenneth P. MacWilliams (Multibeam) *Invited Talk* Presenter: Kokoro Kato (synopsys)	9:00 - 10:35 Session 7 Opening Session Day 2 Defect, Handling, Analysis and Pellicle *Invited Talk* Presenter: Takeshi Kondo (Lintec of America)	9:00 - 9:50 Session 13 Opening Session Day 3 Keynote & mask writer and inspection /metrology to deliver quality content *Keynote* Presenter: David Britz (amat) *Invited Talk* Presenter: Vishal SAROHA (YOLE Group)
11:15 - 11:35 Break	10:35 - 10:55 Break	10:35 - 10:55 Break	9:50 -10:10 Break
11:35 - 12:35 Session 2 Keynote & Energy Sustainability and Productivity *Keynote* Presenter: Mizuki Sakamoto (Tsukuba Univ.)	10:55 - 11:55 Session 8 Mask Metrology	10:55 - 11:45 Session 9 Resist related technologies *Invited Talk* Presenter: Kei Yamamoto (FUJIFILM)	10:10 - 11:25 Session 14 Mask blanks *Invited Talk (BACUS 2024 Best Paper)* Presenter: Seulki Roh (SAMSUNG) *Invited Talk* Presenter: Hanekawa Hiroshi (AGC) Presenter: Rick Jansen (ASML)
12:35 - 13:55 Lunch Break	11:55 - 13:25 Lunch Break	11:45 - 13:25 Lunch Break	11:25 -12:35 Lunch Break
13:55 - 15:05 Session 3 Large size panel technology *Invited Talk* Presenter: Taku Hanna (ulvac) Presenter: Charles Annis (OMDIA)	13:25 - 14:45 Session 10 Mask Inspection *Invited Talk* Presenter: Safak Sayan (intel)	13:25 - 14:50 Session11 NIL *Invited Talk* Presenter: Bríd Connolly (Tekscend Photomask) Presenter: Bo Zhao (Meta)	12:35 -13:40 Session 15 Mask Patterning 2 *Invited Talk (EMLC 2024 Best Oral)* Presenter: Lieve Van Look (imec) 13:40 - 14:00 Break
15:05 - 15:25 Break 15:25 - 16:30 Session 4 Mask Patterning 1 *Invited Talk* Presenter: Aki Fujimura (eBeam Initiative（D2S))	14:45 - 15:00 Break Annex Hall 2F/Foyer 15:00 - 16:20 Session 12 Poster Session		14:00 - 14:45 Session 16 Laser Mask Writing Technology 14:45 - 15:05 Break
16:30 - 16:50 Break 16:50 - 17:55 Session 5 Mask repair *Invited Talk (EMLC 2024 Best Poster)* Presenter: Matthias Roesch (Carl Zeiss SMT)	16:20 - 16:40 Break Annex Hall 2F/Room 1 16:40 - 18:10 Panel Discussion Talent recruiting, education and management in semiconductor/photomask industry		15:05 - 16:25 Session 17 EB Mask Writing Technology *Invited Talk* Presenter: Christoph Spengler (IMS nanofabrication) 16:25 - 16:35 Closing
	Conference Center 5F 18:30 - 20:30 Banquet		